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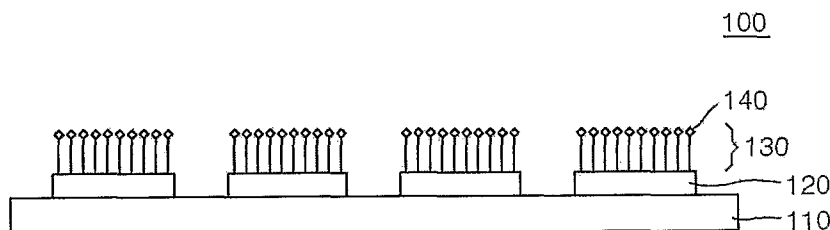
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(54) Title: NANOSTRUCTURE COMPOSITE AND METHOD OF PRODUCING THE SAME

FIG. 1



(57) Abstract: Provided is a nano structure composite and a method of manufacturing the same. More specifically, a nano structure composite that includes a substrate, a first layer formed of carbon nano structures on the substrate, and a second layer formed of metal oxide nano structures on the first layer, and a method of manufacturing the same are provided. When the nano structure composite according to the present invention

is used, a device having a field emission characteristic higher efficiency than a conventional device can be realized, and also, the device can be manufactured at a lower temperature and at a lower pressure. Thus, manufacturing cost can be reduced and a large scale process can be performed.



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A. CLASSIFICATION OF SUBJECT MATTER***B82B 3/00(2006.01)i***

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B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Korean Utility models and applications for Utility models since 1975

Japanese Utility models and applications for Utility models since 1975

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

eKIPASS (KIPO internal) "substrate" "nanowire" "carbon" "catalytic" "CVD"

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
Y	US 2007-0202673 A1, (Dong-Wook Kim et. al.), 30 Aug. 2007 (30.08.2007) see Figure 1, sections [0024] to [[0030], and claims 1 and 2	1-10
Y	KR 1020040107229 A, (Samsung Corning Co., Ltd.), 20 Dec. 2004 (20.12.2004) see pages 3-4 and claims 1-4	1-10



Further documents are listed in the continuation of Box C.



See patent family annex.

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